

3rd Announcement

The 27th Symposium on Photomask and Next Generation Lithography Mask Technology

Photomask Japan 2021 Digital Forum

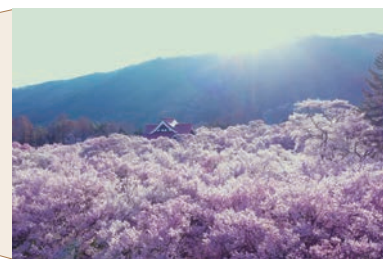
April 20 (Tue.) - 21 (Wed.), 2021

Symposium Chair: Prof. Takeo Watanabe, University of Hyogo (Japan)
Organized by Photomask Japan and SPIE, Co-organized by BACUS and EMLC

Considering the ongoing situation of COVID-19, we have concluded we will not be able to take sufficient safety measures at an in-person symposium. Photomask Japan 2021 will be held fully online on April 20-21. We appreciate your understanding.



You can also enjoy
PMJ movies and
Sakura Drone Movie!



Program

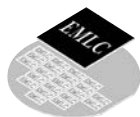
Latest Program <https://www.photomask-japan.org/program.html>

Keynote Speaker: Dr. Klaus Schuegraf (Intel Corporation) The program is subject to change without notice.

Organized by



Co-organized by



Supported by



April 20 (Tue.)				April 21 (Wed.)			
PDT UTC-7	CEST UTC+2	JST UTC+9	Digital Forum	PDT UTC-7	CEST UTC+2	JST UTC+9	Digital Forum
19-Apr 16:00 17:30	20-Apr 1:00 2:30	8:00 - 8:10	Opening	20-Apr 16:00 17:40	21-Apr 1:00 2:40	8:00 - 9:40	Session 7 Opening Session: Day 2
		8:10 - 9:30	Session 1 Opening Session: Day 1				
		9:30 - 9:50	Break			9:40 - 10:00	Break
17:50 18:50	2:50 3:50	9:50 - 10:50	Session 2 ML & MPC	18:00 18:00	3:00 3:00		
		10:50 - 11:10	Break			10:00-12:20	Session 8 NIL
19:10 20:20	4:10 5:20	11:10 - 12:20	Session 3 EUV from Asia 1	20:20 20:20	5:20 5:20		
		12:20 - 13:50	Lunch Break			12:20 - 13:50	Lunch Break
21:50 22:30	6:50 7:30	13:50 - 14:30	Session 4 Lithography	21:50 23:00	6:50 8:00	13:50 - 15:00	Session 9 EUV from Asia 2
		14:30 - 14:50	Break			15:00 - 15:20	Break
22:50 23:50	7:50 8:50	14:50 - 15:50	Session 5 PSM, Etching & FPD	23:20 0:50	8:20 9:50	15:20 - 16:50	Session 10 Inspection
20-Apr 0:10 2:00		15:50 - 16:10	Break	21-Apr 0:50 3:00		16:50 - 17:10	Break
	9:10 11:00	16:10 - 18:00	Session 6 EUV from Europe			17:10 - 18:50	Session 11 Writing & CD Analysis
						18:50 - 19:00	Closing

*Poster presentations will be available from April 20th (JST).

PMJ movies and Sakura movie will be provided during break time.

For registration details, please see <https://www.photomask-japan.org/registration.html>

Technical Exhibition (Online)

- April 20 (Tue.) 9:00- 18:00
- April 21 (Wed.) 9:00- 18:00

For more information, contact:

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